

Silicon Photonic Bragg-Grating add-drop filters and multiplexers using UV lithography

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Abstract: Next generation short reach communication systems require high-performance and low cost optical filters for wavelength division multiplexing. We measured performance of add-drop filters fabricated using a CMOS compatible process. C-band and O-band

Novelty:

1. Rib structure
2. Small features at 1310
3. Large BW and low sidelobes with apodization
4. 1550
5. WDM 4 channels and 2 channels
6. optical litho

1. Introduction

Challenges and state of the art

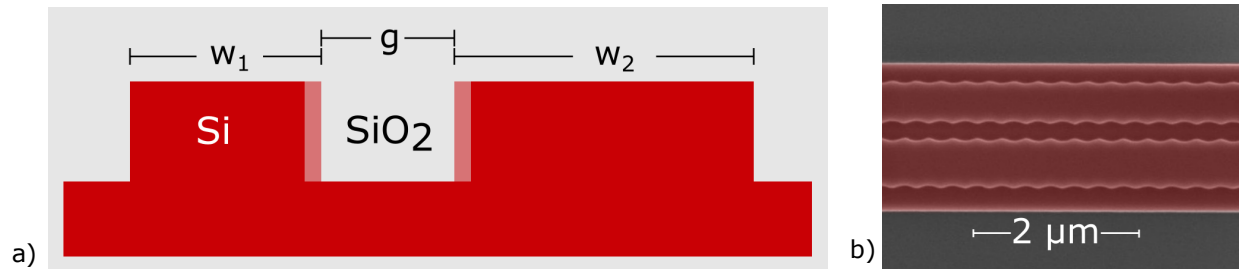


Fig. 1. Schematic cross-section and colored microscope top view of the grating (a) The contra-directional coupler is made of two silicon waveguides of different widths w_1 and w_2 with an average gap g inbetween them. The gap varies along the propagation axis. (b) SEM image shows the shape of the corrugations.

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